

L Number	Hits	Search Text	DB	Time stamp
1	150264	((spin or spinning or rotate or rotating or rotary or rotated or rotate) and (disk or wafer))	EPO; JPO; DERWENT	2003/10/23 13:05
2	838	((spin or spinning or rotate or rotating or rotary or rotated or rotate) and (disk or wafer)) and (temperature near3 (disk or wafer))	EPO; JPO; DERWENT	2003/10/23 12:49
3	56	((spin or spinning or rotate or rotating or rotary or rotated or rotate) and (disk or wafer)) and (temperature near3 (disk or wafer)) and (temperature near3 (resist or photoresist or fluid or liquid))	EPO; JPO; DERWENT	2003/10/23 12:49
4	19	((spin or spinning or rotate or rotating or rotary or rotated or rotate) and (disk or wafer)) and (temperature near3 (disk or wafer)) and (temperature near3 (resist or photoresist or fluid or liquid))) and (thickness)	EPO; JPO; DERWENT	2003/10/23 12:49
5	9181	(temperature near3 (disk or wafer))	EPO; JPO; DERWENT	2003/10/23 12:50
6	331	((temperature near3 (disk or wafer))) and (temperature near3 (resist or photoresist or fluid or liquid))	EPO; JPO; DERWENT	2003/10/23 12:51
7	31	((temperature near3 (disk or wafer))) and (temperature near3 (resist or photoresist or fluid or liquid)) and (thickness)	EPO; JPO; DERWENT	2003/10/23 12:52
8	12	((temperature near3 (disk or wafer)) and (temperature near3 (resist or photoresist or fluid or liquid))) and (thickness) not (((spin or spinning or rotate or rotating or rotary or rotated or rotate) and (disk or wafer)) and (temperature near3 (disk or wafer)) and (temperature near3 (resist or photoresist or fluid or liquid)))) and (thickness))	EPO; JPO; DERWENT	2003/10/23 12:49
9	19771	(temperature near3 (disk or wafer))	USPAT; US-PGPUB	2003/10/23 13:07
10	0	((temperature near3 (disk or wafer))) and (temperature near3 (resist or photoresist or fluid or liquid))	EPO; JPO; DERWENT	2003/10/23 12:51
11	2822	((temperature near3 (disk or wafer))) and (temperature near3 (resist or photoresist or fluid or liquid))	USPAT; US-PGPUB	2003/10/23 12:51
12	827	((temperature near3 (disk or wafer))) same((temperature near3 (resist or photoresist or fluid or liquid)))	USPAT; US-PGPUB	2003/10/23 13:07
13	69	((temperature near3 (disk or wafer))) same((temperature near3 (resist or photoresist or fluid or liquid))) same (thickness)	USPAT; US-PGPUB	2003/10/23 13:01
14	4955	((427/8) or (427/10) or (427/240) or (118/712) or (118/52) or (156/74) or (156/64) or (156/378)).CCLS.	USPAT; US-PGPUB	2003/10/23 13:02
15	332	((427/8) or (427/9) or (427/10) or (427/240) or (118/712) or (118/52) or (156/74) or (156/64) or (156/378)).CCLS.) and @pd>20030310	USPAT; US-PGPUB	2003/10/23 13:04
16	127	((427/8) or (427/9) or (427/10) or (427/240) or (118/712) or (118/52) or (156/74) or (156/64) or (156/378)).CCLS.) and @pd>20030310) and (spin or spinning or rotate or rotating or rotary or rotated or rotate) and (disk or wafer)	USPAT; US-PGPUB	2003/10/23 13:05
17	25	((427/8) or (427/9) or (427/10) or (427/240) or (118/712) or (118/52) or (156/74) or (156/64) or (156/378)).CCLS.) and @pd>20030310) and (spin or spinning or rotate or rotating or rotary or rotated or rotate) and (disk or wafer)) and (temperature near3 (disk or wafer))	USPAT; US-PGPUB	2003/10/23 13:06
18	2831	(temperature near3 (disk or wafer))	USOCR	2003/10/23 13:07

19	482	((temperature near3 (disk or wafer))) near20 (temperature near3 (resist or photoresist or fluid or liquid))	USPAT; US-PGPUB	2003/10/23 13:08
20	79	((temperature near3 (disk or wafer))) near20 (temperature near3 (resist or photoresist or fluid or liquid))	USOCR	2003/10/23 13:08
21	1	((temperature near3 (disk or wafer))) near20 (temperature near3 (resist or photoresist or fluid or liquid))) near20 thickness	USOCR	2003/10/23 13:08